



INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(51) International Patent Classification ⁶ : G03F 7/023	A1	(11) International Publication Number: WO 99/39246 (43) International Publication Date: 5 August 1999 (05.08.99)
(21) International Application Number: PCT/EP99/00343 (22) International Filing Date: 20 January 1999 (20.01.99) (30) Priority Data: 09/017,083 2 February 1998 (02.02.98) US (71) Applicant: CLARIANT INTERNATIONAL LTD. [CH/CH]; Rothausstrasse 61, CH-4132 Muttenz 1 (CH). (72) Inventors: OBERLANDER, Joseph, E.; 31 Wexford Court, Phillipsburg, NJ 08865 (US). RAHMAN, M., Dalil; 62 Concord Ridge Road, Flemington, NJ 08822 (US). COOK, Michelle, M.; 112 Robin Road, No. 221, Somerville, NJ 08876 (US). NELSON, William, C.; 22 Kline Boulevard, Whitehouse Station, NJ 08889 (US). (74) Agent: HÜTTER, Klaus; Clariant GmbH, Patente, Marken und Lizenzen, Room 2027, Building K 801, D-65926 Frankfurt am Main (DE).		(81) Designated States: CN, JP, KR, SG, European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE). Published <i>With international search report. Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>
(54) Title: PROCESS FOR PRODUCING A PHOTORESIST COMPOSITION HAVING A REDUCED TENDENCY TO PRODUCE PARTICLES (57) Abstract A process is provided for producing a photoresist composition having a reduced tendency to produce particles wherein the photoresist composition is filtered through a filter having a rating of from about 0.05 μm to about 0.50 μm ; treated with an acidic ion exchange resin and heated to a temperature of from about 35 °C to about 90 °C; and again filtered through a filter having a rating of from about 0.05 μm to about 0.50 μm .		